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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/652,579	08/31/2000	Vishnu K. Agarwal	98-0616.13	4026
27076	7590 12/17/2003		EXAMINER	
DORSEY & WHITNEY LLP INTELLECTUAL PROPERTY DEPARTMENT SUITE 3400			EVERHART, CARIDAD	
			ART UNIT	PAPER NUMBER
1420 FIFTH	AVENUE	2825		
SEATTLE, WA 98101			DATE MAILED: 12/17/2003	

Please find below and/or attached an Office communication concerning this application or proceeding.

		100				
	Application No.	Applicant(s)				
Office Astion Commons	09/652,579	AGARWAL, VISHNU K.				
Office Action Summary	Examiner	Art Unit				
	Caridad M. Everhart	2825				
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	correspondence address				
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a reply - If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, - Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).  Status	36(a). In no event, however, may a reply be ting within the statutory minimum of thirty (30) day rill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).				
1) Responsive to communication(s) filed on	<u> </u>					
2a)☐ This action is <b>FINAL</b> . 2b)⊠ Th	is action is non-final.					
3) Since this application is in condition for alloward closed in accordance with the practice under a	nnce except for formal matters, p Ex parte Quayle, 1935 C.D. 11, 4	rosecution as to the merits is 453 O.G. 213.				
Disposition of Claims	, , , , , , , , , , , , , , , , , , , ,					
4)⊠ Claim(s) <u>80-84 and 88-110</u> is/are pending in the	ne application.					
4a) Of the above claim(s) is/are withdrawn from consideration.						
5) Claim(s) is/are allowed.						
6)⊠ Claim(s) <u>80-84 and 88-110</u> is/are rejected.						
7) Claim(s) is/are objected to.	7) Claim(s) is/are objected to.					
8) Claim(s) are subject to restriction and/or election requirement.						
Application Papers	_					
9) The specification is objected to by the Examiner.						
10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).  11) The proposed drawing correction filed on is: a) approved b) disapproved by the Examiner.						
If approved, corrected drawings are required in reply to this Office action.						
12) The oath or declaration is objected to by the Examiner.						
Priority under 35 U.S.C. §§ 119 and 120						
13) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).						
a) ☐ All b) ☐ Some * c) ☐ None of:						
1. Certified copies of the priority documents have been received.						
2. Certified copies of the priority documents have been received in Application No						
3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).						
* See the attached detailed Office action for a list of the certified copies not received.						
14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).						
<ul> <li>a) ☐ The translation of the foreign language provisional application has been received.</li> <li>15) ☐ Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.</li> </ul>						
Attachment(s)	_					
<ol> <li>Notice of References Cited (PTO-892)</li> <li>Notice of Draftsperson's Patent Drawing Review (PTO-948)</li> <li>Information Disclosure Statement(s) (PTO-1449) Paper No(s) 2</li> </ol>	5) Notice of Informal	ry (PTO-413) Paper No(s) Patent Application (PTO-152)				
I.S. Detent and Trademark Office						

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The IDS filed 9-2-03 has been reviewed. The cited references are relevant to applicant's disclosure as background references. Li, for example, discloses treatment of a conductive layer with an atmosphere that includes B and the subsequent deposition of a further conductive layer.

Newly found references are applied in rejections follow below.

## - Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

## Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

The factual inquiries set forth in *Graham* v. *John Deere Co.*, 383 U.S. 1, 148 USPQ 459 (1966), that are applied for establishing a background for determining obviousness under 35 U.S.C. 103(a) are summarized as follows:

1. Determining the scope and contents of the prior art.

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- 2. Ascertaining the differences between the prior art and the claims at issue.
- 3. Resolving the level of ordinary skill in the pertinent art.
- 4. Considering objective evidence present in the application indicating obviousness or nonobviousness.

Claims 80,81,88, 89, 96-101, and 105-110 are rejected under 35 U.S.C. 103(a) as being unpatentable over. Sekine, et al. ("Sekine")(US 5,62,888) in view of Zenke (US 5,700,710).

Sekine discloses the steps of depositing a first conductive layer(col. 5, lines 10-14), exposing the wafer in situ to a reducing environment(col. 5, lines 36-44), depositing a second conductive layer(col. 5, lines 35-45). Because of the "comprising" language and the fact that the claim is silent with respect to the order or spatial relationship of the films, there is no order recited or implied in the claims with respect to the first or second conductive films. Therefore, the tungsten film being the one treated in situ with the reducing gas of silane reads on the claims whether the first or second conductive film is recited.

Sekine is silent with respect to exposing one of the layers to phosphine, although Sekine does disclose that the first conductive layer is doped polysilicon(col. 5, lines 65-67), and Sekine further discloses HSG(col. 1, lines 53-57).

Zenke discloses that HSG is formed as the first electrode of a capacitor with anneal of the polysilicon in an atmosphere that includes phospine(col. 4, lines 57-65).

It would have been obvious to one of ordinary skill in the art at the time of the invention to have formed the HSG layer in the method taught by Zenke because Sekine teaches that the lower electrode may be in the form of doped polysilicon and Sekine

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teaches that it is known in the art to use HSG for its large area, which is the goal of the invention disclosed by Sekine, and Zenke teaches a known method to form HSG.

Claims 83,91,94, and 103 are rejected under 35 U.S.C. 103(a) as being unpatentable over Sekine in view of Zenke as applied to claim 80 above, and further in view of Chen, et al. ("Chen")(US 6,077,742).

Sekine in view of Zenke is silent with respect to the borosilicate glass.

Chen discloses a layer of borosilicate glass over capacitors(col. 9, lines 62-67).

One of ordinary skill in the art would have been motivated at the time of the invention to have used a layer of borosilicate glass in the invention disclosed by Sekine in view of Zenke because Sekine teaches an interlayer insulating film(col. 4, lines 53-57) and borosilicate glass is well known in the art, as shown by the fact that Chen suggests this as an interlayer insulating film.

Claims 82,84,90,92,95,102, and 104 are rejected under 35 U.S.C. 103(a) as being unpatentable over Sekine in view of Zenke as applied to claim80 above, and further in view of Lee, et al. ("Lee")(US 2001/0001501A1).

Sekine in view of Zenke does not teach a third conductive layer of polysilicon, although Sekine teaches a third conductive layer of a silicide of a metal such as W(col. 6, lines 45-60).

Lee teaches forming a third conductive layer of polysilicon in a capacitor in which the upper layer can be a multilayer including silicide or polycide of refractory metal, which would include of W.

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One of ordinary skill in the art would have been motivated to have formed the upper layer in the invention disclosed by Sekine in view of Zenke to include polysilicon in view of the disclosure made by Lee because Sekine teaches that the upper layer may be multilayer and can include silicide, which includes silicon, and Lee teaches that the layer may be a multilayer including polycide, which includes silicide. Because both teach that the capacitor includes W, and because one of ordinary skill in the art would have been motivated to have substituted the silicide taught by Sekine with polycide as taught by Lee to be interchangeable with silicide.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Caridad M. Everhart whose telephone number is 703-308-3455. The examiner can normally be reached on Monday through Fridays 7:30-4:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Matthew S. Smith can be reached on 703-308-1323. The fax phone numbers for the organization where this application or proceeding is assigned are 703-872-9318 for regular communications and 703-872-9319 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

12-13-03